

IN THE CLAIMS

Please amend the claims so that they read as shown below.

1 – 26. (canceled)

27. (currently amended) ~~An illumination~~ A projection exposure system, comprising:

an illumination system that includes:

a plate having a plurality of raster elements situated thereon for directing a light beam having a wavelength ≤ 193 nm; ~~and~~

a ~~movable~~ carrier upon which said plate is arranged, for positioning said plate relative to said light beam; and

a reticle plane defined by a y-direction and an x-direction,

wherein said carrier is moveable along a line in said x-direction,

wherein said illumination system illuminates said reticle plane with said light beam, and

wherein said projection exposure system scans said reticle plane in said y-direction.

28. (canceled)

29. (canceled)

30. (currently amended) ~~The illumination~~ projection exposure system of claim ~~29~~ 27, wherein said ~~second direction~~ x-direction is substantially perpendicular to said ~~first direction~~ y-direction.

31. (currently amended) ~~The illumination~~ projection exposure system of claim 27,

wherein said light beam impinges onto said plurality of raster elements, and said plurality of raster elements partition said light beam into a plurality of light bundles, and

wherein said plurality of light bundles substantially overlap one another in ~~a~~ said reticle plane.

32. (currently amended) The ~~illumination~~ projection exposure system of claim 27, wherein said plate is one of a plurality of plates arranged on said carrier.

33. (canceled)

34. (currently amended) The ~~illumination~~ projection exposure system of claim 27, wherein at least one of said plurality of raster elements comprises an actuator for positioning said at least one of said plurality of raster elements relative to said light beam.

35. (currently amended) The ~~illumination~~ projection exposure system of claim 34, wherein said actuator changes an orientation of said raster element relative to said plate.

36. (canceled)

37. (currently amended) A projection exposure system ~~for illuminating a reticle in a reticle plane~~, comprising:

a reticle plane defined by a y-direction and an x-direction; and

an illumination system that includes:

a plate having a plurality of raster elements situated thereon for directing a light beam having a wavelength ≤ 193 nm, and

a table upon which said plate is situated, for moving said plate relative to said light beam, along a line in said x-direction,

wherein said plurality of raster elements partition said light beam into a plurality of light bundles, and

wherein said plurality of light bundles substantially overlap one another in said reticle plane and define a ring field of illumination in said reticle plane, and

wherein said projection exposure system scans said reticle plane in said y-direction.

38. (currently amended) The ~~illumination~~ projection exposure system of claim 37,

~~wherein said plurality of light bundles substantially overlap one another in a reticle plane of said illumination system and define a ring field of illumination in said reticle plane, and~~
wherein at least one of said plurality of raster elements is adjustable to change said ring field of illumination in said reticle plane.

39. (currently amended) The ~~illumination~~ projection exposure system of claim 38, wherein said at least one of said plurality of raster elements, when adjusted to change said ring field of illumination in said reticle plane, also changes an illumination in an exit pupil of said illumination system.

40. (currently amended) The projection exposure system of claim 38, wherein said at least one of said plurality of raster elements is tiltable.

41. (currently amended) The projection exposure system of claim 38, wherein said at least one of said plurality of raster elements is displaceable.

42. (currently amended) The projection exposure system of claim 38, wherein said at least one of said plurality of raster elements is replaceable.

43 – 46. (canceled)

47. (currently amended) A projection exposure apparatus, comprising:

(a) an illumination system for illuminating an object in a reticle plane with light having a wavelength \leq 193 nm,

wherein said reticle plane is defined by a y-direction and an x-direction,

wherein said illumination system includes (i) a plate having a plurality of raster elements situated thereon, and (ii) a ~~movable~~ carrier upon which said plate is arranged, for positioning said plate relative to a beam of said light, wherein said carrier is movable along a line in said x-direction,
and

wherein said projection exposure apparatus scans said reticle plane in said y-direction; and

(b) a projection objective for imaging said object onto a light sensitive substrate.

48. (previously presented) The projection exposure apparatus of claim 47, wherein said object is a pattern-bearing mask.

49. (currently amended) A method for manufacturing a microelectronic component, comprising using an projection exposure apparatus having:

- (a) an illumination system for illuminating an object in a reticle plane with light having a wavelength \leq 193 nm,

wherein said reticle plane is defined by a y-direction and an x-direction,

wherein said illumination system includes (i) a plate having a plurality of raster elements situated thereon, and (ii) a ~~movable~~ carrier upon which said plate is arranged, for positioning said plate relative to a beam of said light, wherein said carrier is movable along a line in said x-direction, and

wherein said projection exposure apparatus scans said reticle plane in said y-direction; and

- (b) a projection objective for imaging said object onto a light sensitive substrate.

50. (currently amended) The ~~illumination~~ projection exposure system of claim 27,

wherein said plurality of raster elements is a first plurality of raster elements, and

wherein said illumination system further comprises:

a second plurality of raster elements that receives said light beam from said first plurality of raster elements.

51. (currently amended) The ~~illumination~~ projection exposure system of claim 27, wherein said plurality of raster elements is a plurality of reflective raster elements.

52. (currently amended) The projection exposure system of claim 37, wherein said plurality of raster elements is a plurality of reflective raster elements.

53. (previously presented) The projection exposure apparatus of claim 47, wherein said plurality of raster elements is a plurality of reflective raster elements.

54. (previously presented) The method of claim 49, wherein said plurality of raster elements is a plurality of reflective raster elements.

55. (currently amended) ~~An illumination~~ A projection exposure system, comprising:
an illumination system for illuminating a reticle plane defined by a y-direction and an x-direction, wherein
said illumination system includes:

a first plate having a first plurality of raster elements situated thereon for directing a light beam
having a wavelength ≤ 193 nm;

a ~~movable~~ carrier upon which said first plate is arranged, for positioning said plate relative to
said light beam, wherein said carrier is moveable along a line in said x-direction, and;

a second plate having a second plurality of raster elements that receives said light beam from
said first plurality of raster elements, wherein said second plate is in a fixed position,
wherein said projection exposure system scans said reticle plane in said y-direction.

56. (currently amended) ~~The illumination~~ projection exposure system of claim 55,
wherein said first plurality of raster elements produces a plurality of images of a source of said light, and
wherein said second plurality of raster elements is situated at or near said plurality of images.